

<b>INFORMATION DISCLOSURE STATEMENT</b>	<b>Atty. Docket No.:</b> 150.00800102	<b>Serial No.:</b> 09/651,702
	<b>Applicant(s):</b> Brian A. VAARTSTRA	
	<b>Filing Date:</b> August 30, 2000	<b>Group:</b> 1756

#4  
**U.S. PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Name	Class	SubClass	Filing Date If Appropriate
nb	4,296,146	10/20/81	Penn	427	38	
	4,778,536	10/18/88	Grebinski	134	36	
	4,861,424	08/29/89	Fujimura et al.	156	643	
	4,944,837	07/31/90	Nishikawa et al.	156	643	
	5,013,366	05/07/91	Jackson et al.	134	1	
	5,037,506	08/06/91	Gupta et al.	156	643	
	5,298,112	03/29/94	Hayasaka et al.	156	643	
	5,382,316	01/17/95	Hills et al.	156	643	
	5,401,322	03/28/95	Marshall	134	13	
	5,403,436	04/04/95	Fujimura et al.	156	643	
	5,643,474	7/1/97	Sangeeta	216	96	
	5,651,860	07/29/97	Li	156	643	
	6,024,801	02/15/00	Wallace et al.	134	1	
nb	6,149,828	11/20/00	Vaartstra	216	57	

**FOREIGN PATENT DOCUMENTS**

Document Number	Date	Country	Class	SubClass	Translation
					Yes No
nb WO 95/20476	08/03/95	PCT			

**OTHER DOCUMENTS (Including Authors, Title, Date, Pertinent Papers, etc.)**

nb	G. Bakker et al., "Removal of Thermally Grown Silicon Dioxide Films Using Water at Elevated Temperature and Pressure", <u>J. Electrochem. Soc.</u> , 142(11), 3940-3944 (1995).
nb	M. Dax, "Removing Photoresist Without Plasmas or Liquid Strippers," <u>Semiconductor International: Contamination Control News</u> , 52 (September 1996).
nb	Deal et al., "Vapor Phase Wafer Cleaning: Processing for the 1990s," <u>Solid State Technology</u> , 73-77 (July 1990).
nb	T. Nolan, "Economic Geology and the Bulletin of the Society of Economic Geologists", 45(7), Title Page, Table of Contents, pgs. 601, 629-653 (1950).

**EXAMINER****Date Considered**


2/21/02

\*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.